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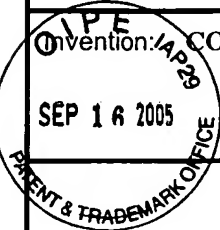
WU, Ives J.

Group Art Unit

1713

Invention: COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME

SEP 16 2005

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PATENT ABSTRACTS OF JAPAN

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(21)Application number : 07-284281 (71)Applicant : SHIN ETSU CHEM CO LTD

(22)Date of filing : 27.09.1995 (72)Inventor : TSUCHIYA JUNJI

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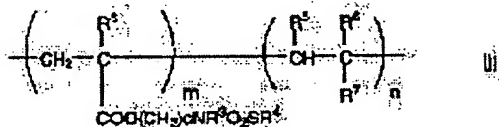
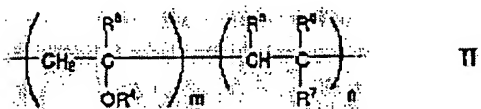
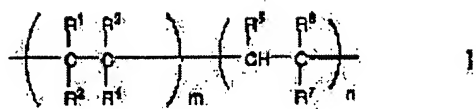
ISHIHARA TOSHINOBU

(54) REFLECTION PREVENTIVE FILM MATERIAL AND PATTERN FORMING METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To enhance the dimensional precision and lamination accuracy by using a fluoro-resin made of a copolymer of a specified fluorinated vinyl monomer and a vinyl monomer having a hydrophilic group, such as carboxy or sulfo, for a reflection preventive film material.

SOLUTION: A water-soluble fluoro-resin expressed by formulae I-III is used as a main component. In the formulae I-III, each of R1 and R2 is H or F atom; R3 is H atom or a trifluoromethyl group or the like; R4 is -(CH2)8-(CF2)bX group or the like; R5 is H atom or a carboxy group or the like; R6 is H atom or methyl group or the like; R7 is a carboxy or sulfo group or the like; R8 is H atom or methyl group; R9 is H atom or a 1-6C alkyl group; X is H or F atom; each of (a), (b), and (c) is an integer of 0-2, 1-8, and 2-5, respectively; and a ratio of (m) to (n) is 1:9-9:1.



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